






NITRILE/FLUOROALCOHOL-CONTAINING PHOTORESISTS AND ASSOCIATED PROCESSES FOR MICROLITHOGRAPHY**Publication number:** JP2004500596 (T)**Publication date:** 2004-01-08**Inventor(s):****Applicant(s):****Classification:**

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Nitrile/fluoroalcohol-containing photoresists and associated processes for microlithography are described. These photoresists are comprised of a fluoroalcohol functional group and a nitrile-containing compound which together simultaneously impart high ultraviolet (UV) transparency and developability in basic media to these materials. The materials of this invention have high UV transparency, particularly at short wavelengths, e.g., 157 nm, which makes them highly useful for lithography at these short wavelengths.

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AND ASSOCIATED PROCESSES FOR MICROLITHOGRAPHY**

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